2:30 D-61 **GRAZING-INCIDENT X-RAY DIFFRACTION ANALYSES OF NOVEL MAGNETIC THIN FILMS**—*Invited*

K. Inaba, Y. Ito, K. Omote, H. Toraya, *Rigaku Corporation, Tokyo, Japan*

3:00 D-12 **ULTRA-FAST SIMULTANEOUS FITTING OF SEVERAL BRAGG REFLECTIONS FROM AlAs/GaAs SUPERLATTICES USING METHOD OF EIGENWAVES**

A. Ulyanenkov, R. Eisenhower, I. Feranchuk, H. Guérault, H. Ress, *Bruker AXS, Karlsruhe, Germany*

3:20 **Break**

3:50 D-5 **THE DIRECT DETERMINATION OF X-RAY DIFFRACTION DATA FROM SPECIFIC DEPTHS**

A. Broadhurst, K.D. Rogers, D.W. Lane, T.W. Lowe, *Cranfield Univeristy, Swindon, UK*

4:10 D-70 **"BaF_2 PROCESS": PHASE EVOLUTION OF $Ba_2YCu_3O_{6+X}$ FILMS**

W. Wong-Ng, I. Levin, M.D. Vaudin, L.P. Cook, *National Institute of Standards & Technology, Gaithersburg, MD*

R. Feenstra, *Oak Ridge National Laboratory, Oak Ridge, TN*

4:30 D-89 **IN-SITU HTXRD CHARACTERIZATION FOR THIN FILMS**

E.A. Payzant, S.A. Speakman, *Oak Ridge National Laboratory, Oak Ridge, TN*

XRD

Wednesday p.m. **Twilight**

Session D-1 ✤ Small Angle Scattering

Organized by: **N.S. Murthy**, University of Vermont, Burlington, VT
J.D. Londono, DuPont Company, Wilmington, DE

2:00 D-108 **IN SITU STUDIES OF NANO-PARTICLE GROWTH IN FLAMES**—*Invited*

G. Beaucage, N. Agashe, *University of Cincinnati, Cincinnati, OH*

H.K. Kammler, S.E. Pratsinis, *Institute of Process Engineering, ETH Zentrum, Zurich, Switzerland*

J. Ilavsky, P. Jemian, *UNICAT, Advanced Photon Source, Argonne, IL*

T. Narayanan, *ID02, European Synchrotron Research Facility, Grenoble, France*

D. Londono, *Dupont Experimental Station, Wilmington, DE*

2:30 D-106 **IN-SITU STRUCTURAL STUDIES OF SEMICRYSTALLINE POLYMER BLENDS USING SYNCHROTRON RADIATION**—*Invited*

P. Thiyagarajan, S. Seifert, *Argonne National Laboratory, Argonne, IL*

M. Kipper, B. Narasimhan, *Iowa State University, Ames, IA*

3:00 D-91 **LOOKING AT SMALL HOLES: CROSS-VALIDATION OF SAXS- AND BET-POROSIMETRY**

P. Laggner, *Austrian Academy of Sciences, Graz, Austria and Hecus X-ray Systems GmbH, Graz, Austria*

3:20 **Break**

3:40 D-101 **FROM LAB TO FAB: THE DEVELOPMENT AND DEPLOYMENT OF NEW METROLOGY TECHNOLOGY FOR THE GLOBAL SEMICONDUCTOR INDUSTRY**—*Invited*

B. Landes, B. Kern, J. Niu, C. Mohler, J. Hahnfeld, D. Yontz, K. Ender, C. Silvis, R. Strittmatter, L. Moore, T. Stokich, D. King, *Dow Chemical Co., Midland, MI*

J. Quintana, S. Weigand, *Northwestern University, Chicago, IL*

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